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Introduction

The International Symposium on Optoelectronic Technology and Application 2018 (OTA 2018) is the annual conference of the Chinese Society for Optical Engineering. It continues to be one of the largest academic and industrial conferences in the field of optical and optoelectronic technology in China. This year's program included academic exchanges, industry exhibitions, and cooperation negotiations together in one event. There were five technical conferences, seven exhibition themes, and 600 technical negotiations. We sincerely hope that this event continues to promote research and development of optoelectronic technology and to enhance international cooperation in the optical and optoelectronic fields.

OTA 2018 was sponsored by The Division of Information and Electronic Engineering of the Chinese Academy of Engineering (China), and The Chinese Society for Optical Engineering (CSOE) (China). The conference was organized by the Chinese Society for Optical Engineering (CSOE) (China), the Photoelectronic Technology Committee, the Chinese Society of Astronautics (China), the Photoelectronic Industrialization Committee, CHIA (China), the Department of Cooperation and Coordination for Industry, Academe, and Research, CHIA (China), and the Science and Technology on Low-light-level Night Vision Laboratory (China). We received more than 759 contributions from more than 15 countries, including the United States, United Kingdom, Germany, France, Spain, Australia, Canada, Mexico, Brazil, Japan, Republic of Korea, Thailand, Singapore, Russian Federation and China. There were more than 400 contributions published in SPIE Proceedings, including 70 contributions from invited speakers. After careful discussion, six keynote speeches were selected and presented by famous scientists from the United States, United Kingdom, Republic of Korea, and China. There were 138 excellent invited talks, 45 from overseas, that reflected first-class level in the field of optics and photonics technology. On behalf of the OTA 2018 Organizing Committee, I would like to express thanks to all the invited speakers and authors for their contributions and support.

Finally, on behalf of the other Co-chairmen and the Organizing Committee, I would like to heartily thank our sponsors and cooperating organizers for all they have done for the conference, and to all of the participants and friends for their interests and efforts in helping us to make the conference a success. Thanks also to the Program Committee for their effective work and valuable advice, especially the Secretariat, and to the staff of SPIE for their tireless efforts and outstanding service preparing and publishing the proceedings.

We hope to see you next year!

Guangjun Zhang